

IN THE CLAIMS:

1. (Currently Amended) A manufacturing apparatus for a semiconductor device ~~wherein~~ comprising:

a plurality of semiconductor manufacturing and processing apparatuses are installed in a clean room, comprising:

an external air cleaning device connected to a supply port of said clean room for supplying a cleaned-up outside air into said clean room;

an air duct comprising a common air duct section for ~~constructing~~ providing a common air pass path to said plurality of semiconductor manufacturing and processing apparatuses in said clean room and ~~an~~ a plurality of individual air duct section sections, each of which are branched off from said common air duct section for ~~constructing~~ providing an individual air ~~pass path~~ pass path to ~~each~~ only a corresponding portion of said plurality of semiconductor manufacturing and processing apparatuses;

pre-stage air cleaning and ventilating means having a chemical filter and a fan for further cleaning a part of said cleaned-up outside air supplied by said external air cleaning device ~~at an entrance of said common air duct section; and~~

post-stage air cleaning and ventilating means having a fan filter unit at ~~each~~ one or more of said individual air duct ~~section sections~~ sections for supplying a further cleaned-up ~~outside air by said~~ supplying said post-stage air cleaning and ventilating means to each of said plurality of semiconductor manufacturing and processing apparatuses.

2. (Currently Amended) The manufacturing apparatus as cited in Claim 1, ~~wherein~~ said post-stage air cleaning and ventilating means includes a ~~minute difference~~ pressure damper.

3. (Currently Canceled)

4. (Currently Canceled)

5. (Currently Amended) A manufacturing apparatus for a semiconductor device comprising:

a clean room ~~for installing~~ having a plurality of semiconductor manufacturing and processing apparatuses;

an external air cleaning device connected to a supply port of said clean room for supplying a cleaned-up outside air into said clean room;

a common air duct section installed in said clean room;

a first air cleaning and ventilating means connected to said common air duct section for further cleaning and ventilating a part of said cleaned-up outside air ~~from said external air cleaning device to and supplying to~~ said common air duct section;

one or more individual air duct ~~section~~ sections branched off from said common air duct section and connected to ~~each~~ only a corresponding portion of said semiconductor manufacturing and processing apparatuses; and

~~a-at least one~~ second air cleaning and ventilating means ~~interposed between said~~ associated with one or more individual air duct ~~section~~ sections ~~and each of said semiconductor manufacturing and processing apparatuses for further cleaning and ventilating the air to be supplied to each of said semiconductor manufacturing and processing apparatuses.~~

6. (Original) The manufacturing apparatus as cited in Claim 5, wherein said external air cleaning device includes a fine grain eliminating filter for cleaning up and supplying the outside air into said clean room.

7. (Currently Amended) The manufacturing apparatus as cited in Claim 6, wherein said first air cleaning and ventilating means includes: ~~;~~ : a chemical filter means and ventilation means for further cleaning up said part of said cleaned-up outside air from said external air cleaning device ~~and ventilating to said common air duct section.~~

8. (Currently Amended) The manufacturing apparatus as cited in Claim 7, wherein said second air cleaning and ventilating means includes: a fan filter unit for further cleaning up the air ~~from~~ for its said individual air duct section ~~means and ventilating to each of said semiconductor manufacturing and processing apparatuses.~~

9. (Currently Amended) The manufacturing apparatus as cited in Claim 8, wherein said second air cleaning and ventilating means includes a ~~minute difference~~ pressure damper.

10. (Canceled)

11. (Canceled)